

<b>Notice of References Cited</b>	Application/Control No. 10/642,607	Applicant(s)/Patent Under Reexamination VAARTSTRA ET AL.	
	Examiner Christy L. Novacek	Art Unit 2822	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-5,877,087	03-1999	Mosely et al.	438/656
	C	US-			
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	K	US-			
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

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#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Ward et al., "New Developments in CVD Source Delivery and Source Reagents", Semiconductor Fabtech Journal, Edition 1, Section 5, Sept. 1994
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.